

# Graphene Oxide Paste / Slurry and Graphene Oxide Liquid

## Equipment used

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RAMAN	: BRUKER SENTERRA II -Confocal Raman Microscope
AFM	: Park Systems XE 100 Atomic Force Microscope
XPS	: Thermo Scientific™ ESCALAB™ Xi+ X-ray Photoelectron Spectrometer
XRD	: BRUKER D8 Focus X-ray diffractometer
FTIR	: BRUKER Vertex80 FTIR microscope (Hyperion)

## Sample Details

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**Start-up Graphite** : C99+ Vein Graphite, Particle size range: 63-90  $\mu\text{m}$

<b>Product</b>	GO Paste
<b>Color</b>	Brown
<b>Odor</b>	Odorless
<b>Initial Moisture Content (%)</b>	85 - 95
<b>GO Content (g/kg)</b>	150 - 50
<b>pH range (at 25 °C)</b>	2 - 3

## Graphene Oxide Liquid:

**Graphene Oxide Concentration can be customized to any percentage.**

Our Liquid standard is based on 1% concentration (10g/L) paste.

If requires 2% (20g/L) concentration paste or Concentration 3.5% (35g/L), or any Percentage per customer requirements.

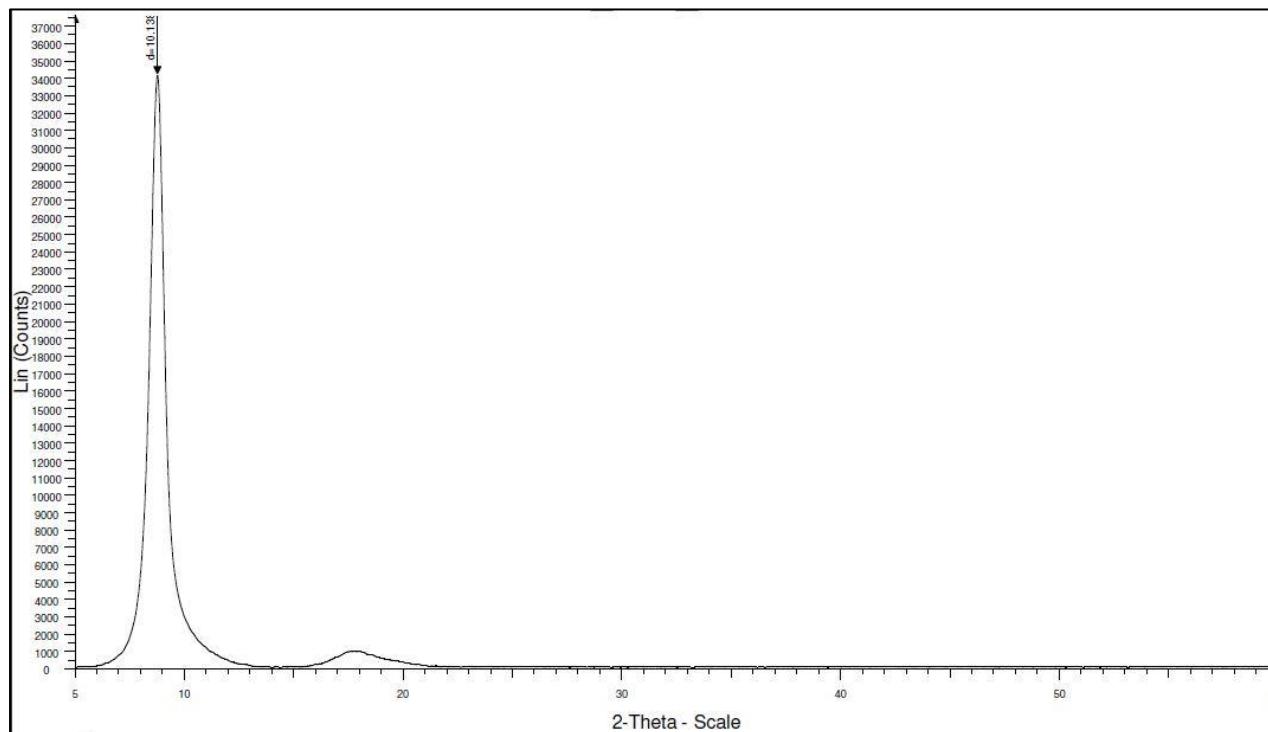
Dry content based pricing.

## Analysis

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### X-ray powder diffraction (XRD)

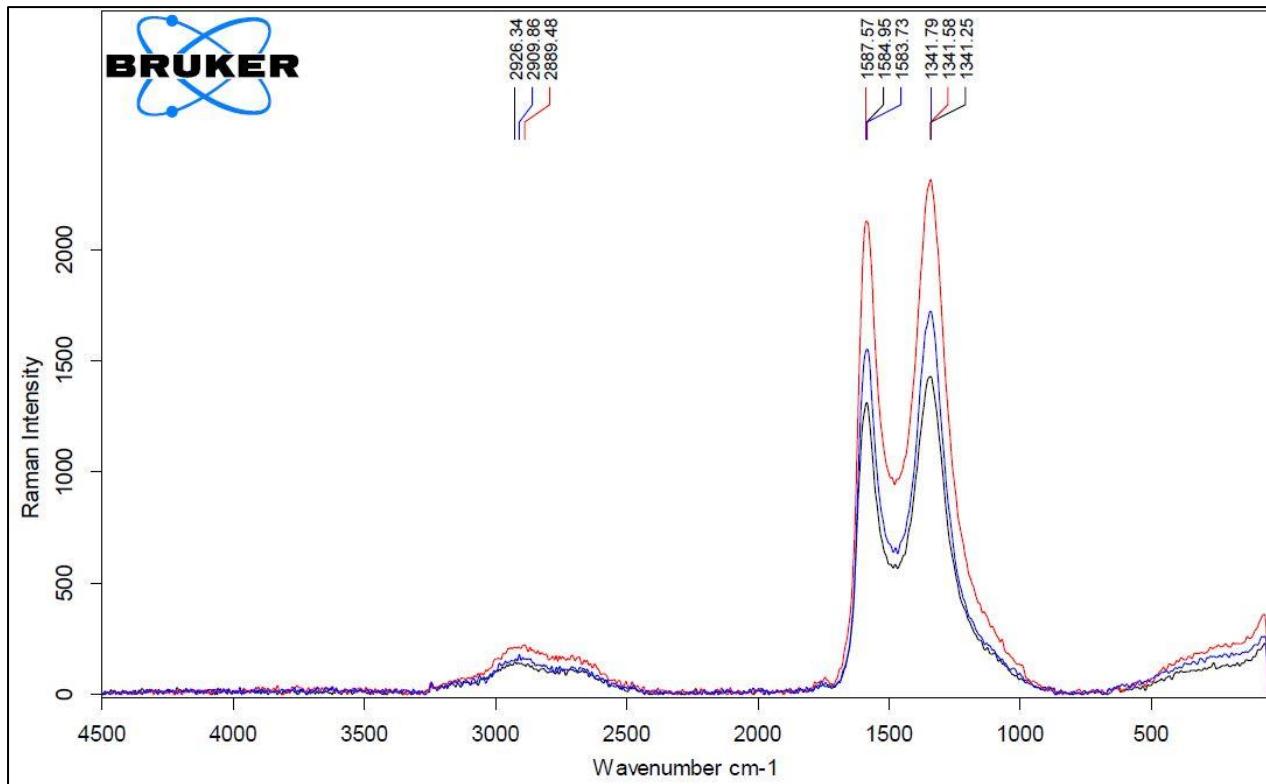
The sample was mounted on sample holder. Parameters were set as follows, Cu K $\alpha$  radiation ( $\lambda=0.154$  nm) over a  $2\theta$  range of 5–60° with a step size of 0.02° and a step time of 10 s.



**d-spacing 9 - 10 Å**

## RAMAN Analysis

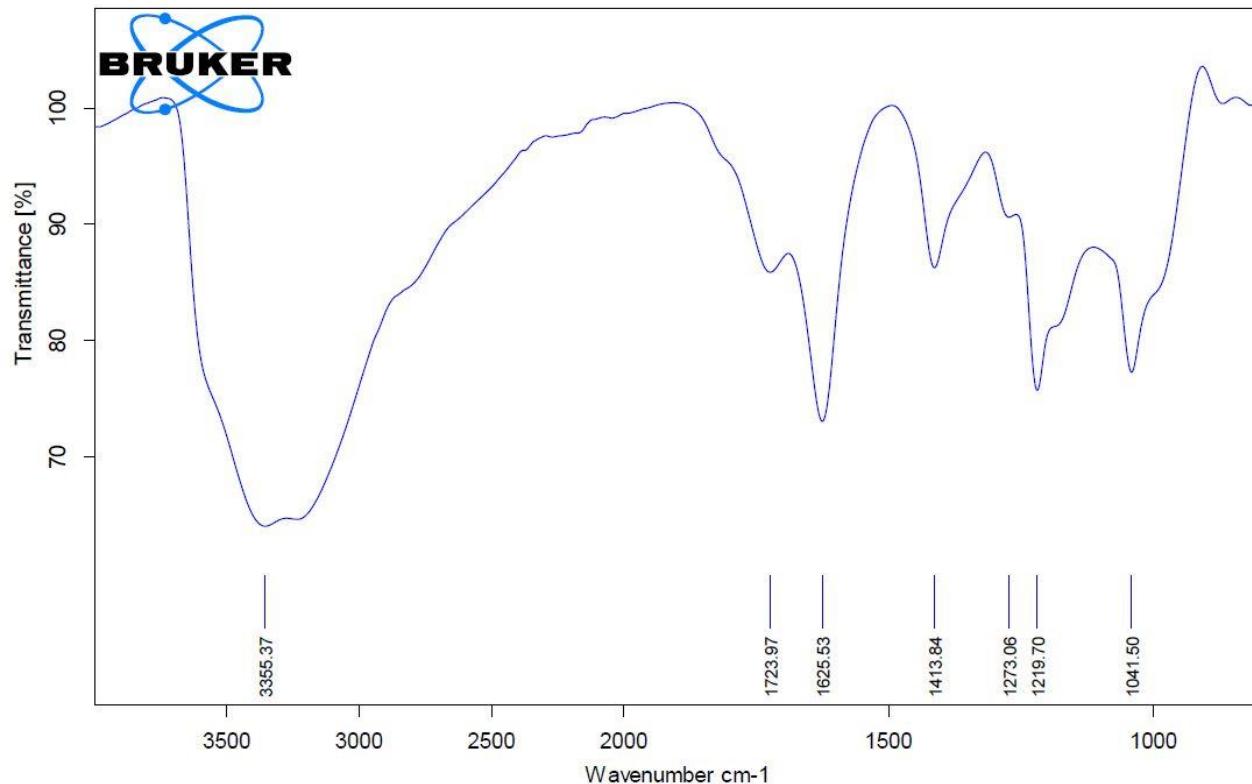
The sample was drop casted on  $\text{SiO}_2$  wafers whose oxide thickness is 300 nm. Three different spots were analyzed. Parameters were set as follows, 532 nm; green laser was used with 20X optical zooming.



**Average  $I_d/I_g$  ratio: 1.01 – 1.10**

## Fourier-transform infrared spectroscopy (FTIR)

Attenuated total reflection Fourier transform infrared (ATR-FTIR) spectra of the graphene oxide were recorded in the region 800 to 4000  $\text{cm}^{-1}$  at a resolution of 4  $\text{cm}^{-1}$ .

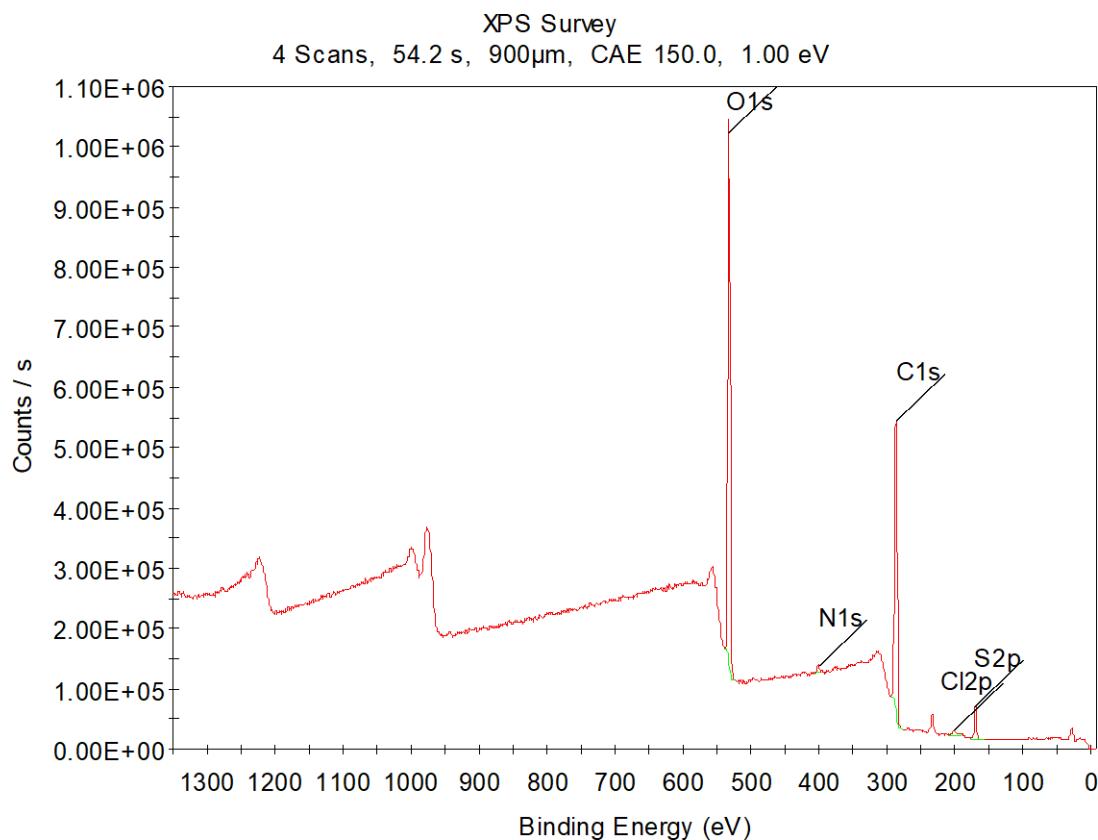


## X-ray Photoelectron Spectroscopy (XPS)

The sample was mounted on a glass substrate using double tape. Three different spots per sample were analyzed. Parameters were set as follows, X-Ray source: Monochromatic Al K $\alpha$  (1486.6 eV), Spot size: 900  $\mu$ m. Survey scans and high-resolution scans were collected with pass energies of 150 and 20 eV and with a step size of 1.0 and 0.05 eV. Detailed spectra processing was performed by Thermo Avantage (5.982) software.

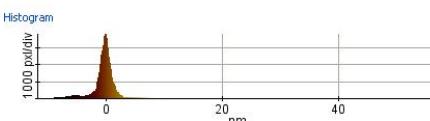
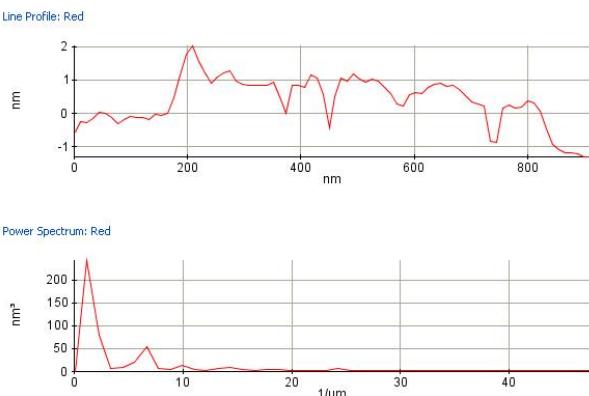
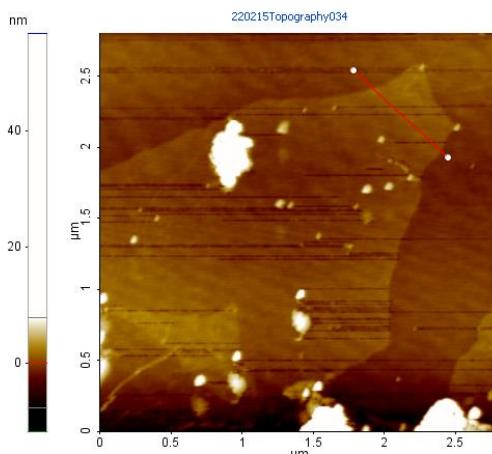
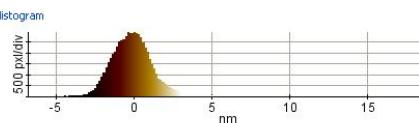
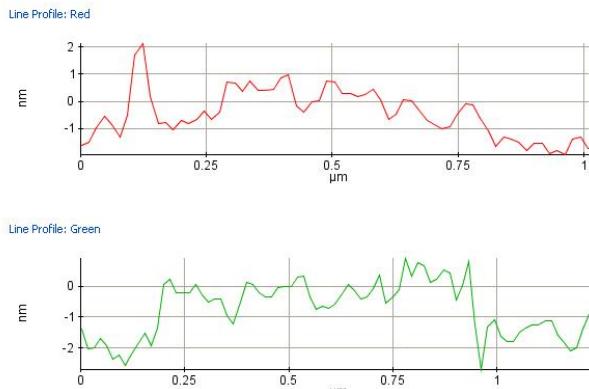
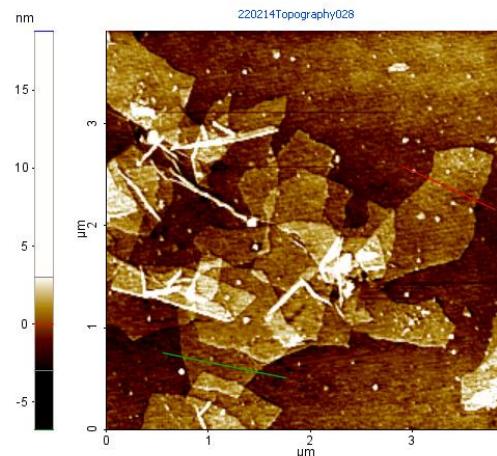
Name	Peak BE	Atomic %			Avg. %
		scan 1	scan 2	scan 3	
O1s	531.77	34.12	34.76	33.73	34.20
C1s	285.1	62.16	61.27	62.24	61.89
N1s	399.93	0.56	0.82	0.79	0.72
S2p	168.39	2.85	2.78	2.77	2.80
Cl2p	199.44	0.31	0.37	0.47	0.38

\*C/O ratio: 1.80 – 2.40



## Atomic Force Microscopic (AFM) Analysis

The sample was drop casted on a 300 nm (Oxide thickness) Silicon Dioxide Wafer of dimension 1 cm  $\times$  1 cm. The concentration of the GO Dispersion prepared was 0.01 mg/ml.



**Average Through Plane Dimension (Z – axis)**  
**Average Lateral Dimension ( X & Y axis)**

= ~ 2.0 nm  
 = 1 - 2 μm